

AMENDMENT

IN THE CLAIMS:

Please amend the claims as follows:

1. (Currently amended) A plasma processing ~~unit~~ system comprising:

- a processing container whose inner pressure can be reduced,
- a first electrode arranged in the processing container, ~~for placing a substrate to be processed thereon~~ the first electrode being supplied a first high-frequency electric power and a second high-frequency electric power,
- a process gas supplying ~~unit~~ part that supplies a process gas into the processing container,
- a tubular supporting part that supports the first electrode, the tubular supporting part forming an enclosed space together with a bottom surface of the first electrode such that said enclosed space is disposed within the tubular supporting part below the first electrode, and
- a high-frequency electric power supplying part arranged in the enclosed space, ~~including a first high-frequency electric power source that outputs first high-frequency electric power having a first frequency,~~
 - ~~the first high-frequency electric power transmitted from the first high-frequency electric power source to the first electrode is adapted to generate plasma in such a manner that the substrate to be processed can undergo a plasma process by means of the plasma, and~~
 - wherein the high-frequency electric power supplying part further includes comprises:
 - a first high-frequency electric power source unit that outputs the first high-frequency electric power having a first frequency,
 - a first matching unit for impedance matching of the first high-frequency electric power,
 - a second matching unit for impedance matching of the second high-frequency electric power, and
 - a transmission line that transmits the first high-frequency electric power from the first high-frequency electric power source unit to the first matching unit.

2. (Withdrawn) A plasma processing unit according to claim 1, wherein the length of the

transmission line is shorter than $\lambda/2$, λ being a wavelength of the third harmonic wave of the high-frequency electric power, and with respect to the third harmonic wave of the high-frequency electric power, an output terminal of the high-frequency electric power source and an input terminal of the matching unit are electrically short-circuited ends, respectively.

3. (Currently amended) A plasma processing ~~unit~~system according to claim 1, wherein the transmission line has a length which is shorter than $3\lambda/4$, λ being a wavelength of a third harmonic wave of the first high-frequency electric power, and

with respect to the third harmonic wave of the first high-frequency electric power, an output terminal of the high-frequency electric power source is an electrically short-circuited end and an input terminal of the first matching unit is an electrically open end.

4. (Currently amended) A plasma processing ~~unit~~system according to claim 1, wherein the first high-frequency electric power source ~~includes~~ comprises:

a first high-frequency electric power generating part that generates the first high-frequency electric power when direct-current power is supplied thereto, and

a filter that selectively allows the first high-frequency electric power from the first high-frequency electric power generating part to pass therethrough.

5. (Currently amended) A plasma processing ~~unit~~system according to claim 4, wherein

the first high-frequency electric power source further ~~includes~~ comprises a circulator that allows a forward wave from the first high-frequency electric power generating part to pass therethrough and that absorbs a reflected wave from the first matching unit, between the first high-frequency electric power generating part and the filter.

6. (Currently amended) A plasma processing ~~unit~~system according to claim 1, wherein the transmission line consists of a coaxial cable.

7. (Currently amended) A plasma processing ~~unit~~system according to claim 1, wherein the first

frequency is not less than 70 MHz.

8. (Currently amended) A plasma processing ~~unit-system~~ according to claim 1, wherein

a second electrode is arranged in the processing container in parallel with and opposed to the first electrode.

9. (Currently amended) A plasma processing ~~unit-system~~ according to claim 8, wherein

the substrate to be processed is adapted to be placed on the first electrode, and a vent hole is provided in the second electrode to jet out the process gas toward the first electrode.

10. (Canceled)

11. (Currently amended) A high-frequency electric power supplying ~~unit~~ apparatus, comprising:

a first high-frequency electric power source unit that outputs first high-frequency electric power having a first frequency,

a first matching unit for impedance matching of the ~~first-frequency~~ high-frequency electric power,

a second matching unit for impedance matching of second high-frequency electric power,

and

a transmission line that transmits the first high-frequency electric power from the first high-frequency electric power source unit to the first matching unit,

wherein[:]

the high-frequency electric power supplying ~~unit~~ apparatus is arranged in an enclosed space and further arranged for a plasma processing ~~unit-system~~, the plasma processing system comprising-unit-including:

a processing container whose inner pressure can be reduced;

a first electrode arranged in the processing container, the first electrode being supplied the first high-frequency electric power and the second high-frequency electric power, for placing a substrate to be processed thereon;

a process gas supplying unit apparatus that supplies a process gas into the processing container; and

a tubular supporting part that supports the first electrode, the tubular supporting part forming the enclosed space together with a bottom surface of the first electrode such that said enclosed space is disposed within the tubular supporting part below the first electrode;

~~wherein the first high-frequency electric power transmitted from the first high-frequency electric power source to the first electrode is adapted to generate plasma in such a manner that the substrate to be processed can undergo a plasma process by means of the plasma;~~

~~further wherein the transmission line has a length which is shorter than $3\lambda/4$, λ being a wavelength of a harmonic wave of the first high-frequency electric power, and with respect to the third harmonic wave of the first high-frequency electric power, an output terminal of the first high-frequency electric power source is an electrically short-circuited end and an input terminal of the first matching unit is an electrically open end.~~

12. (Withdrawn): A high-frequency electric power supplying unit according to claim 11, wherein the length of the transmission line is shorter than $\lambda/2$, λ being a wavelength of the third harmonic wave of the high-frequency electric power, and with respect to the third harmonic wave of the high-frequency electric power, an output terminal of the high-frequency electric power source and an input terminal of the matching unit are electrically short-circuited ends, respectively.

13. (Canceled)

14. (Currently amended) A high-frequency electric power supplying unit according to claim 11, wherein the first high-frequency electric power source ~~includes~~ comprises:

a first high-frequency electric power generating part that generates the first high-frequency electric power when direct-current power is supplied thereto, and

a filter that selectively allows the first high-frequency electric power from the first high-frequency electric power generating part to pass therethrough.

15. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to claim 14, wherein

the first high-frequency electric power source further ~~includes~~comprises a circulator that allows a forward wave from the first high-frequency electric power generating part to pass therethrough and that absorbs a reflected wave from the first matching unit, between the first high-frequency electric power generating part and the filter.

16. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to claim 15,

wherein the first high-frequency electric power generating part is connected via a cable to a direct-current power source that converts alternating-current power of commercial frequency into the direct-current power.

17. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to claim 11, wherein

the transmission line consists of a coaxial cable.

18. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to claim 11, wherein

the first frequency is not less than 70 MHz.

19. (Currently amended) A plasma processing ~~unit~~system according to claim 4, wherein

the filter has an output terminal connected to the transmission line as an electrically short-circuited end with respect to a harmonic wave of the first high-frequency electric power.

20. (Canceled)

21. (Currently amended) A plasma processing ~~unit~~ system according to ~~claim 20~~ claim 1,

wherein

the high-frequency electric power supplying part has three vertically-stacked boxes; and the first high-frequency electric power source, the first matching unit and the second matching unit are contained in the three boxes, respectively.

22. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to claim 14, wherein

the filter has an output terminal connected to the transmission line as an electrically short-circuited end with respect to a harmonic wave of the first high-frequency electric power.

23. (Canceled)

24. (Currently amended) A high-frequency electric power supplying ~~unit~~apparatus according to ~~claim 23~~ claim 11, wherein

the high-frequency electric power supplying part has three vertically stacked boxes; and the first high-frequency electric power source, the first matching unit and the second matching unit are contained in the three boxes, respectively.

25. (New) A high-frequency electric power supplying apparatus according to claim 11, wherein the transmission line has a length which is shorter than $3\lambda/4$, λ being a wavelength of a harmonic wave of the first high-frequency electric power, and

with respect to the third harmonic wave of the first high-frequency electric power, an output terminal of the first high-frequency electric power source is an electrically short-circuited end and an input terminal of the first matching unit is an electrically open end.